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IN THE U.S. PATENT AND TRADEMARK OFFICE

April 3, 2001

Applicant(s):

Toshiaki MOTONAGA et al.

For

HALFTONE PHASE SHIFTING PHOTOMASK AND

BLANKS FOR HALFTONE PHASE SHIFTING

PHOTOMASK THEREFOR AND A METHOD FOR FORMING

PATTERN BY USING THE HALFTONE PHASE

SHIFTING PHOTOMASK

Atty. Docket No.: OPS Case 529

Assistant Commissioner for Patents

Washington, DC 20231

AMENDMENT BEFORE FIRST OFFICE ACTION

Sir:

Prior to issuance of the first Office Action in the above-identified application, kindly enter the following:

## IN THE SPECIFICATION

Paragraphs 0029, 0030, 0035, 0036 and 0038-0040 are amended as indicated in the attached marked-up copy. Pursuant to 37 CFR §1.121, replacement pages with the amended paragraphs are attached.

## REMARKS

The above amendment is being made to conform the brief descriptions of Figs. 1, 2, 5, 7, 8 and 10-12 to the drawing sheets.

Respectfully submitted,

Thiel

DHT/jp

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Reg. No. 36 328

Req. No. 31 257 Reg. No. 24 949 Reg. No. 40 694

Reg. No. 24 323

Reg. No. 25 072

Req. No. 22 724

Reg. No. 32 549

Req. No. 36 589

Encl: Marked-up paragraphs 0029, 0030, 0035, 0036

and 0038-0040 (2 pages)

Replacement paragraphs 0029, 0030, 0035, 0036

and 0038-0040 (2 pages)